



Laser-assisted direct-writing of thermoelectric generators

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Outline

1. Motivation
2. Laser-induced forward transfer
3. Thermoelectric generator designs
4. Results
5. Comparison with existing generators
6. Conclusion

1. Motivation (I)



Thermoelectric generation (TEG) via
Seebeck effect

Current thermoelectric (TE) research:

- Increasing efficiency of **materials** (lowering thermal conductivity & electrical resistivity, increasing Seebeck coefficient).
- New, inexpensive and non-toxic materials
- **Devices** with increased power density (via scaling, packaging) + novel manufacturing methods

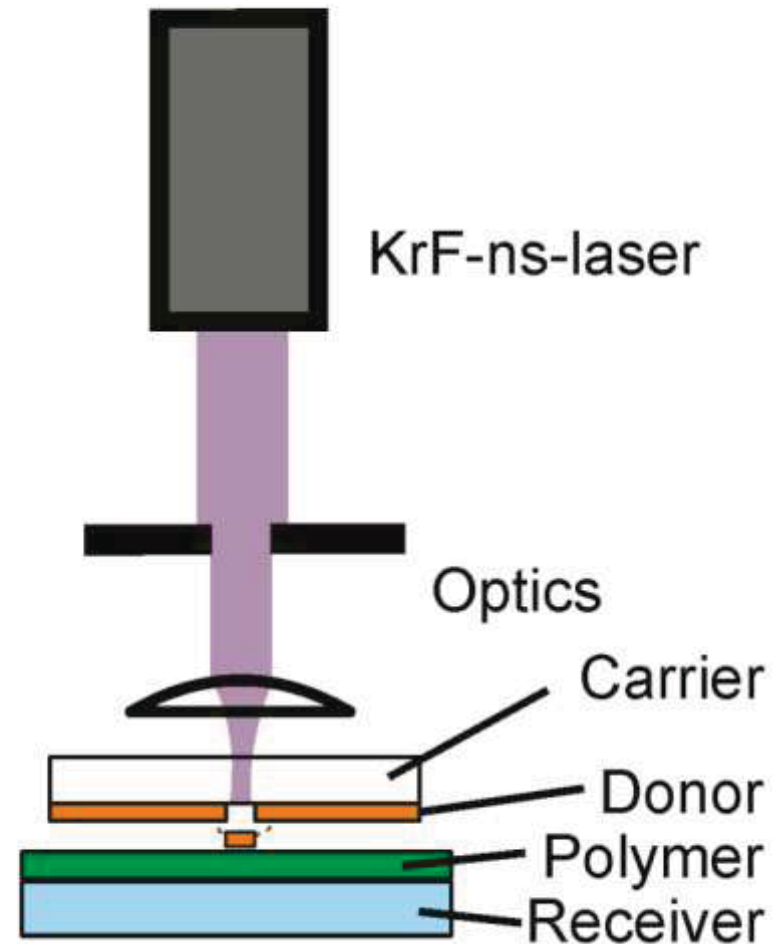
1. Motivation (II)

- **Reduce complexity** in manufacturing (using a laser-assisted transfer technique):
 - **Sequential** transfer
 - **Fast** deposition (Single laser pulse process)
- **Combine complex materials in device**
 - **Intact transfer** of solid material onto polymer
 - **Preserving** phase of material

 **Objective: Fabricate and test working thermoelectric generator via laser-induced forward transfer**

2. Laser-induced forward transfer

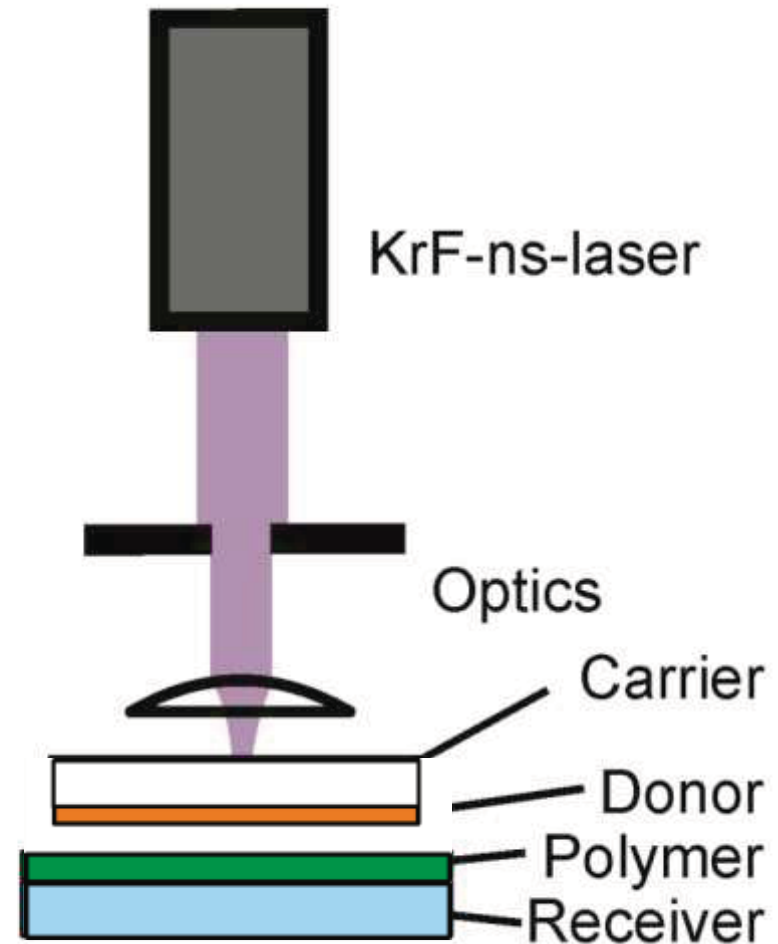
- Laser-induced forward transfer (LIFT)
- **Additive direct-write**
- **Thin film** technique for the fabrication of electronic devices
- Transfer **solid** materials in **intact** state
- Preserve physical properties of donor



2. Laser-induced forward transfer

Experimental:

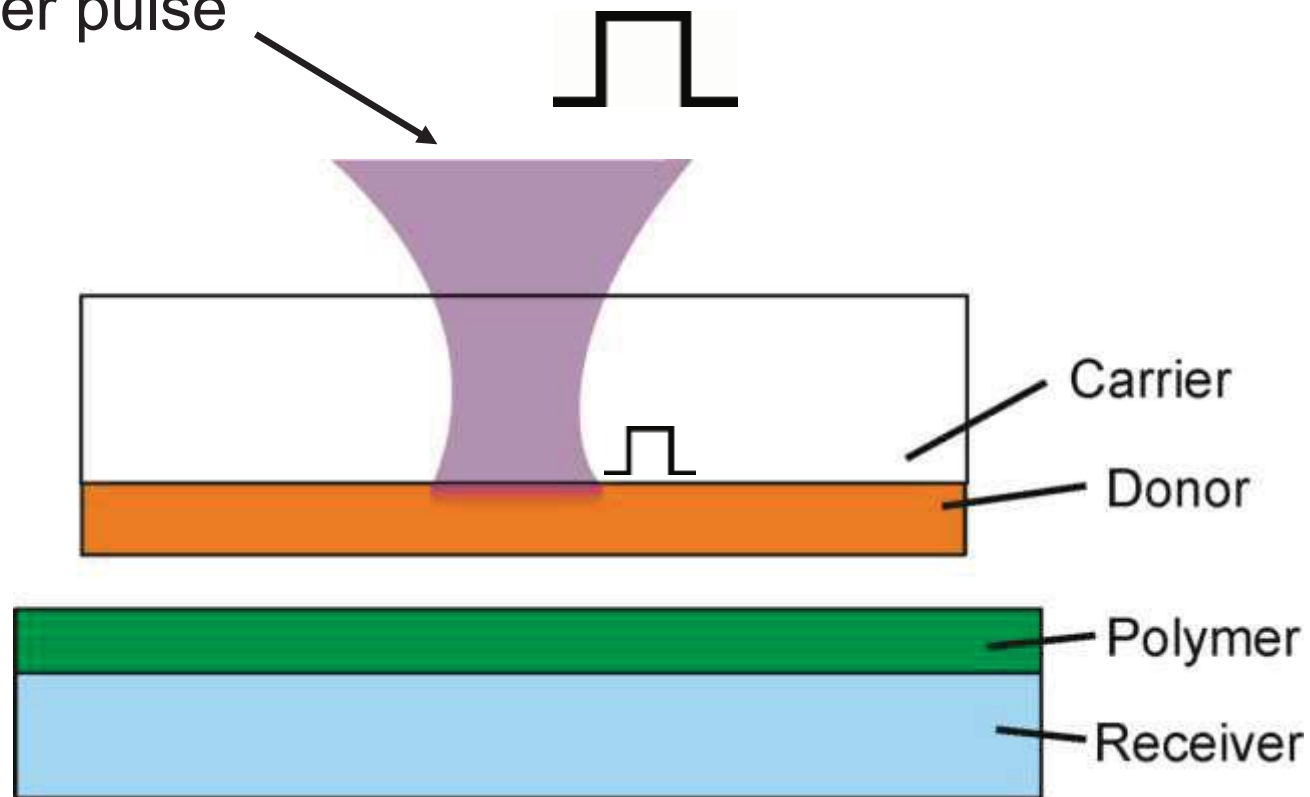
- UV excimer laser system, 248nm
- 20ns pulses, max. 0.4J pulse energy, 3x demagnification
- Typical donor/receiver spacing of some microns or in contact.



2. Principle of LIFT

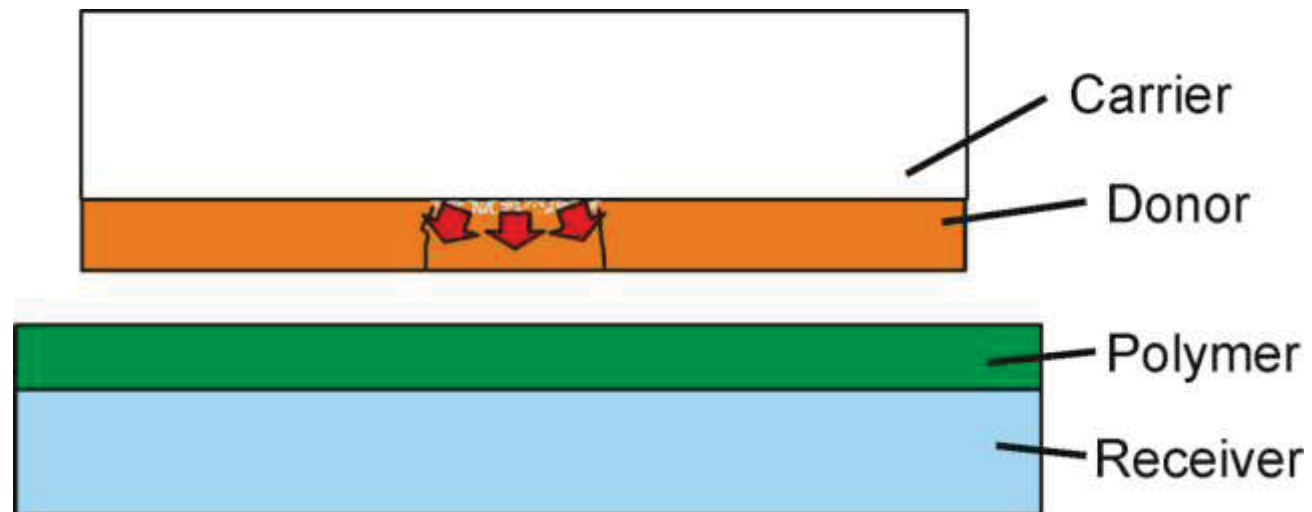
1) Absorption

Laser pulse



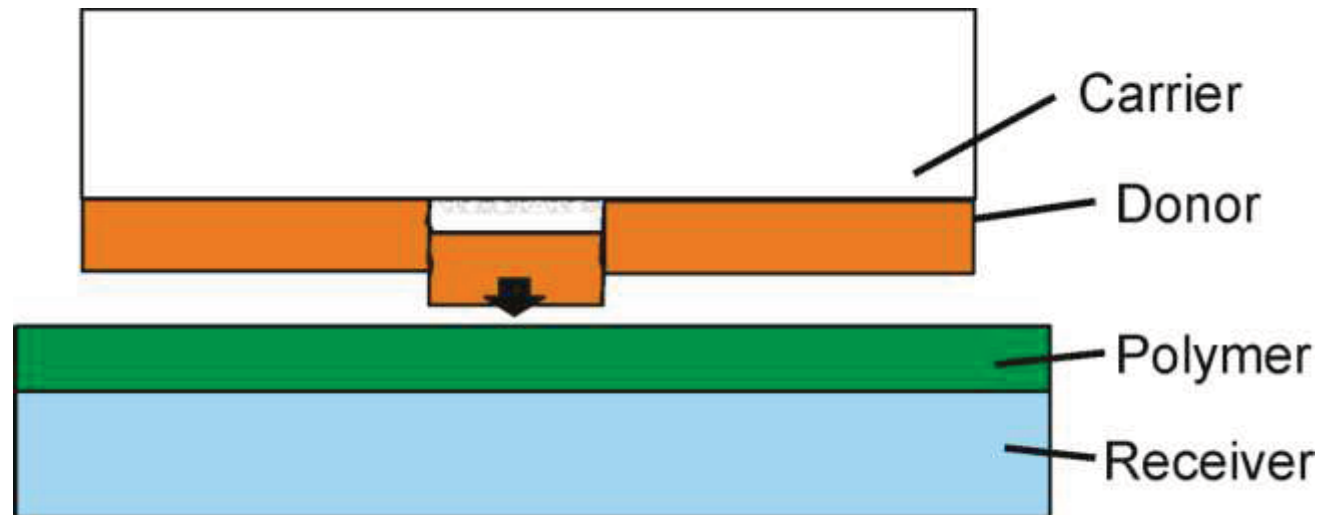
2. Principle of LIFT

2) Pressure build-up

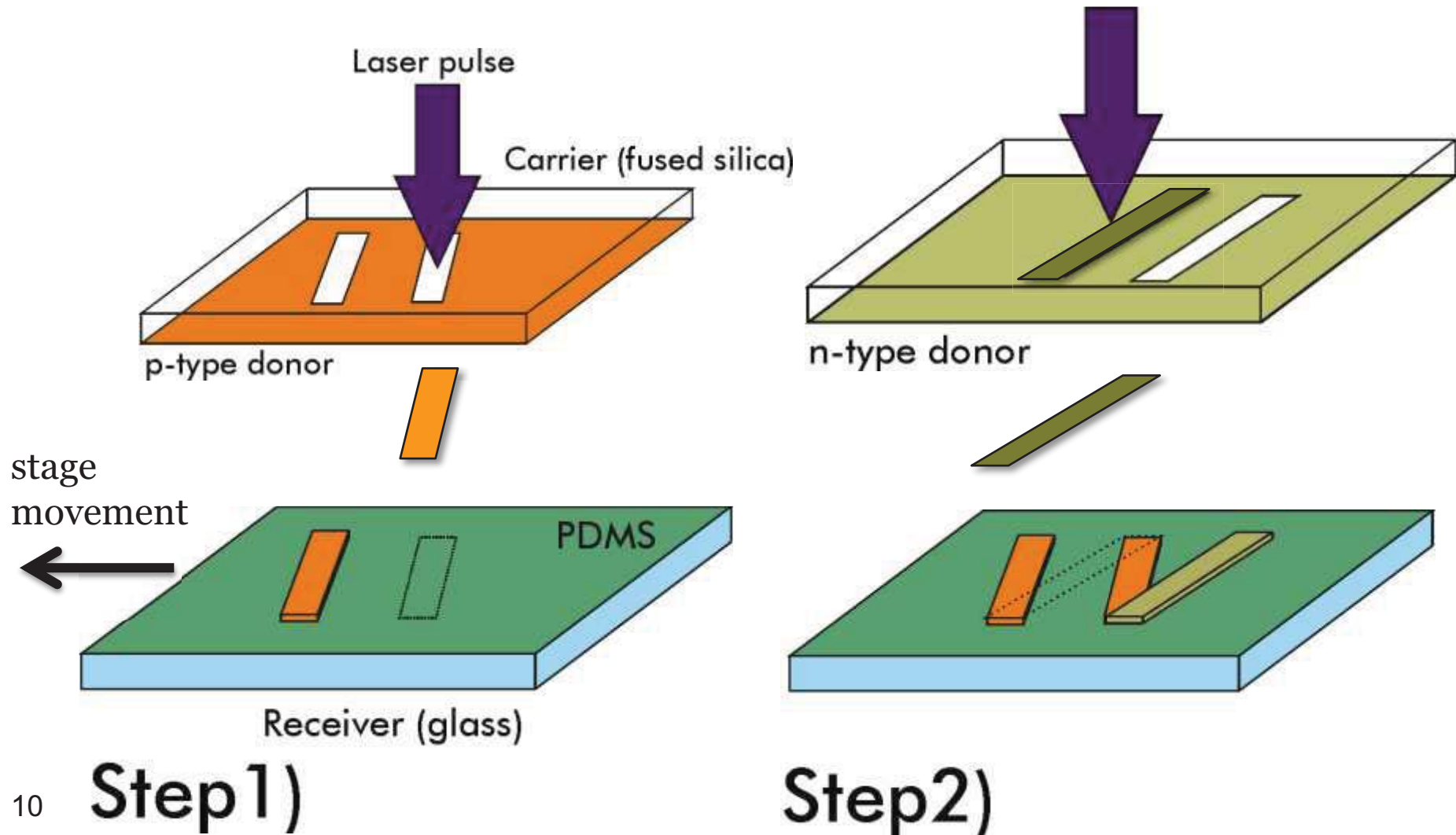


2. Principle of LIFT

3) Transfer

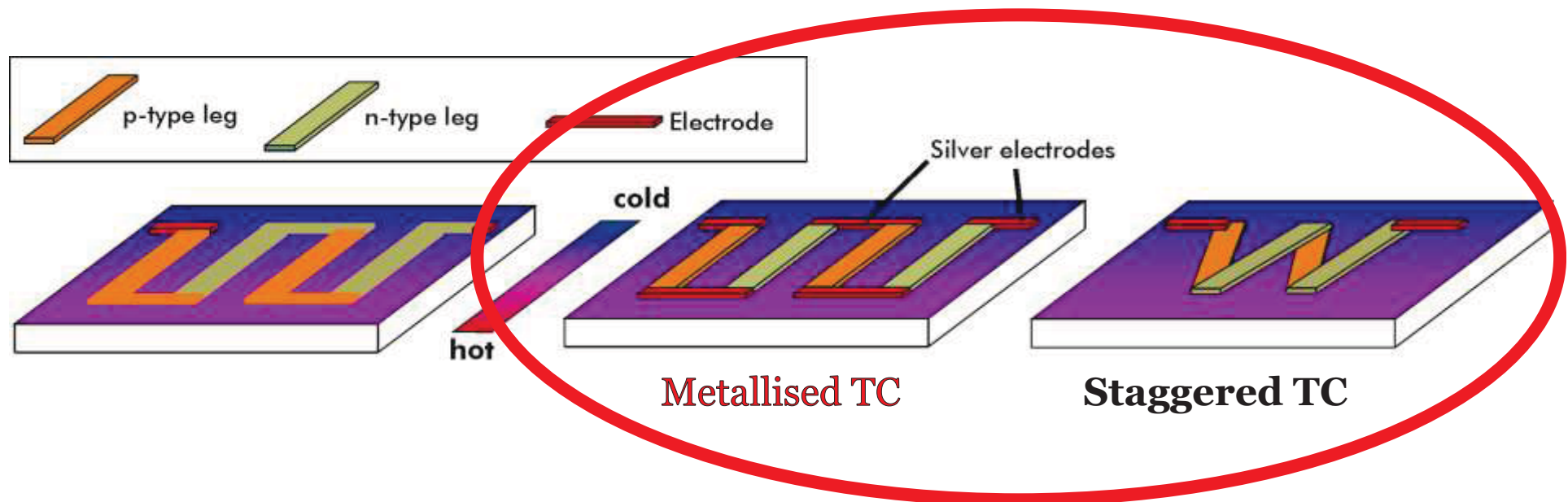


2. Sequential transfer

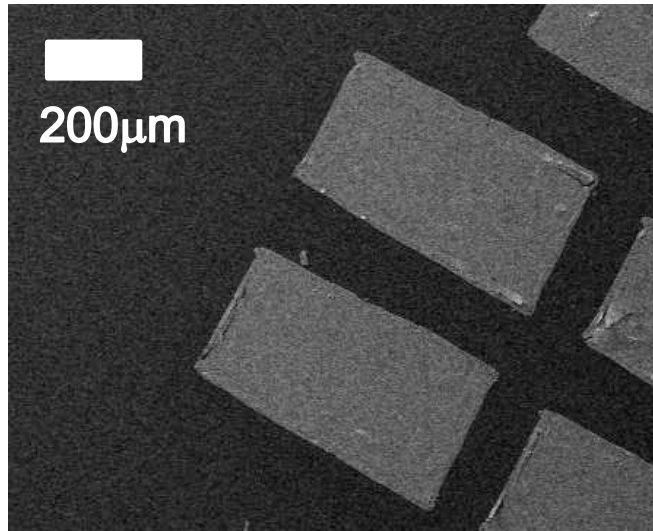


3. Designs of TEG

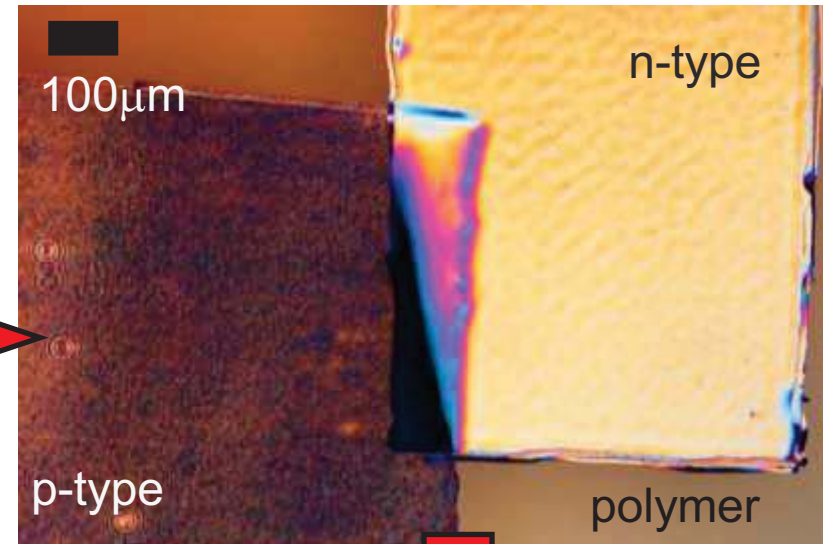
- Lateral-lateral design: heat and current flow in substrate plane
- Design chosen as most common thermoelectric thin film device technology
- Two designs: **Silver (Ag)-contacted & staggered thermocouples (TC)**



4. Results- Morphology



**This
work**

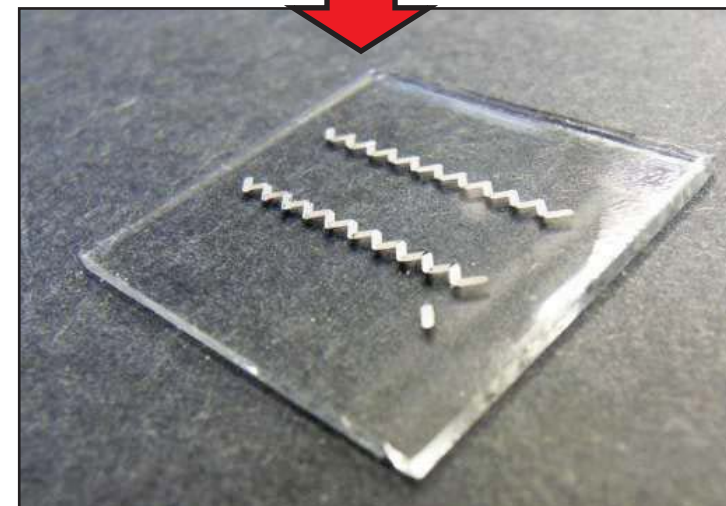


Feinaeugle et al., Appl Phys A (2012)

Deposition of chalcogenides (Bi_2Se_3 , Bi_2Te_3 and $\text{Bi}_{0.5}\text{Sb}_{1.5}\text{Te}_3$) via LIFT without intermediate release layer onto polydimethylsiloxane (PDMS)-coated glass substrate:

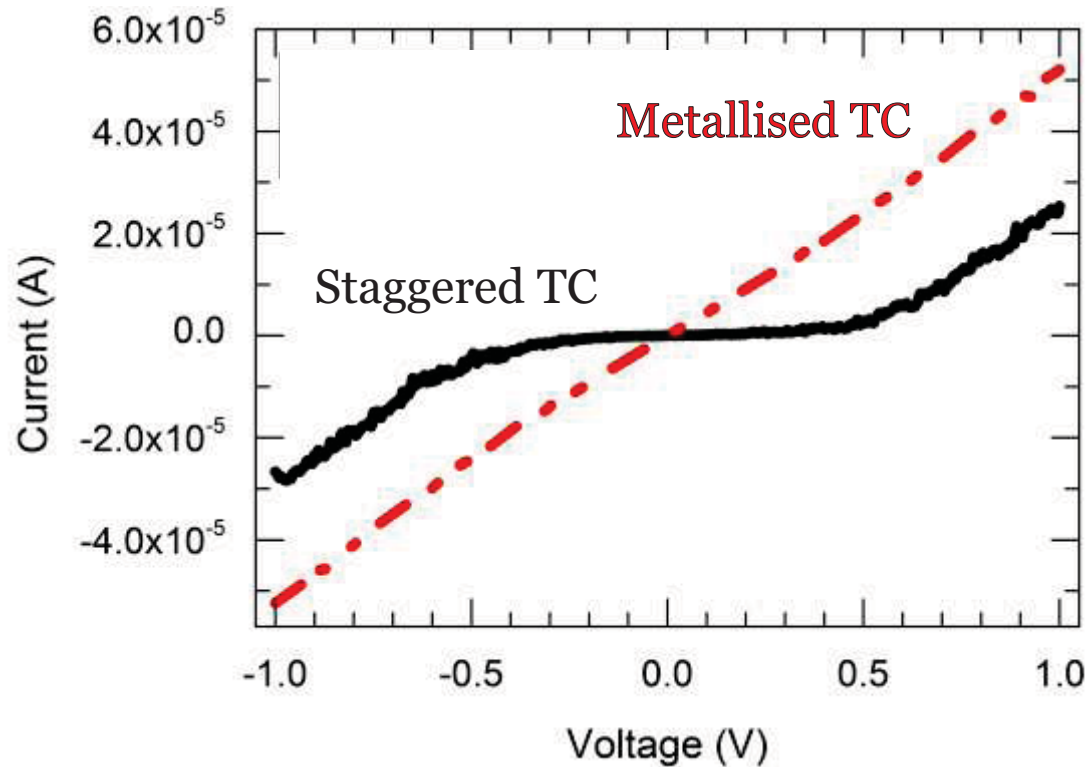
- Preservation of >75% of Seebeck coefficient
- Deposited areas up to 15mm^2 area

12



Substrate size: ~25mm x 20mm

4. Electrical characterisation

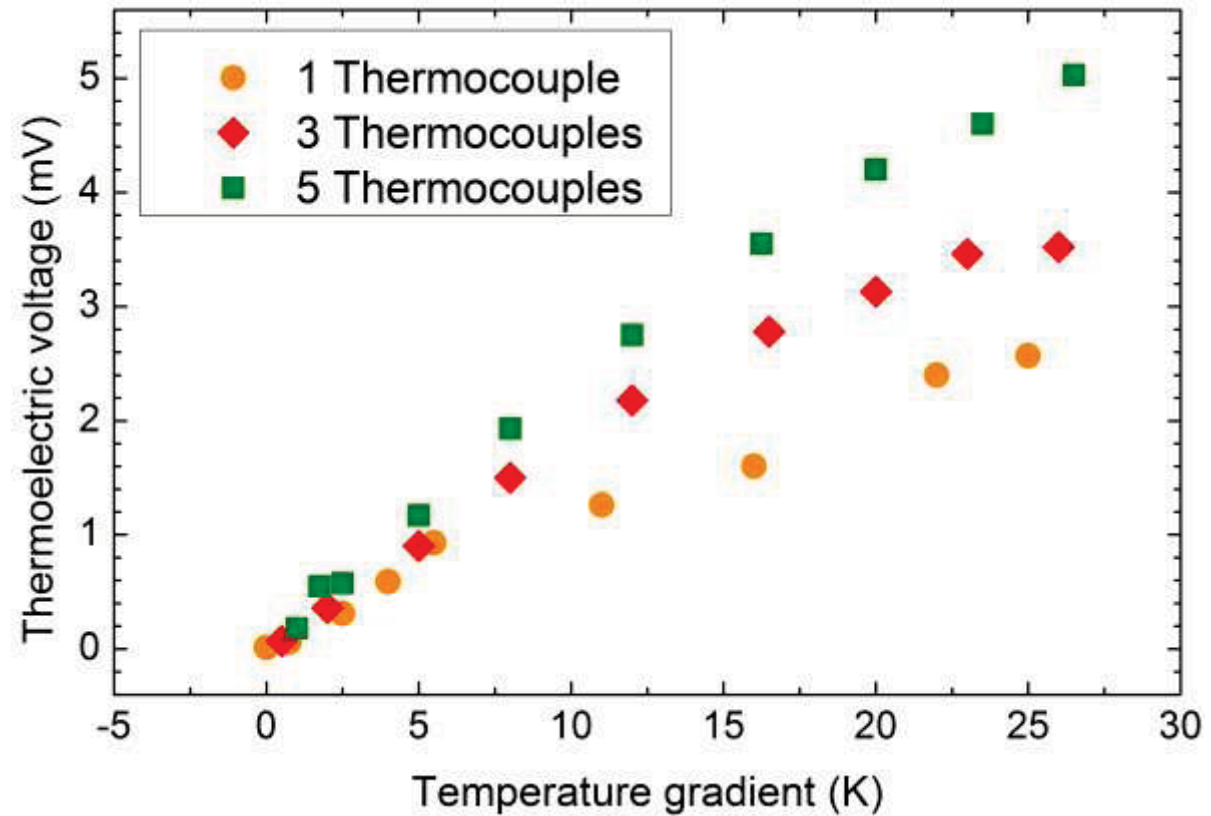
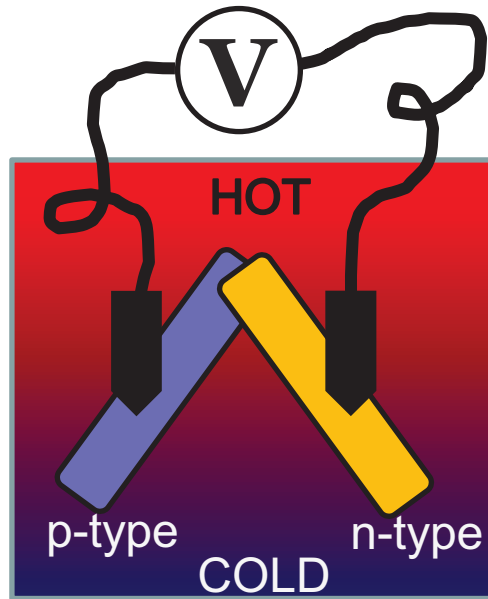


For single TC:

- Contact resistance (staggered TC) $\sim 2\text{k}\Omega$
- Total resistance: $9\text{k}\Omega$
- Large TE element resistance due to non-optimised materials

Material	Resistivity [Ωm] ($\pm 10\%$)	Seebeck coefficient (donor) [μVK^{-1}] ($\pm 5\%$)	Seebeck coefficient (deposit) [μVK^{-1}] ($\pm 5\%$)
Bi_2Se_3	0.04	-121	-93
Bi_2Te_3	0.003	-64	-49
$\text{Bi}_{0.5}\text{Sb}_{1.5}\text{Te}_3$	0.0006	+177	+142

4. Thermoelectric measurements

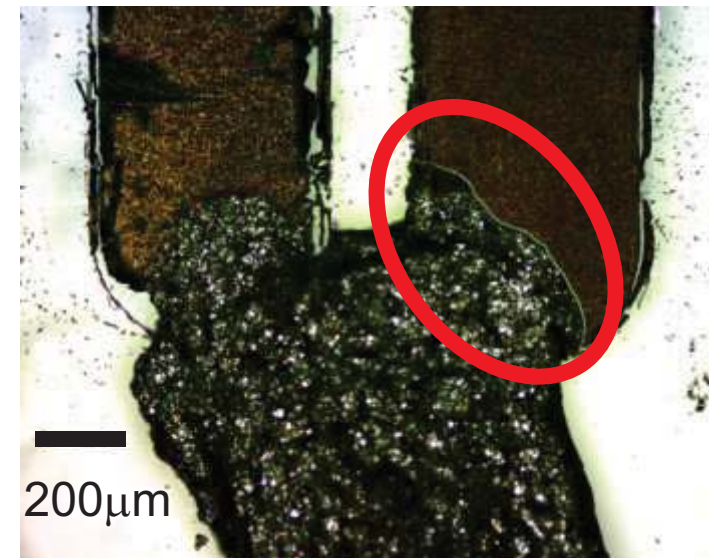
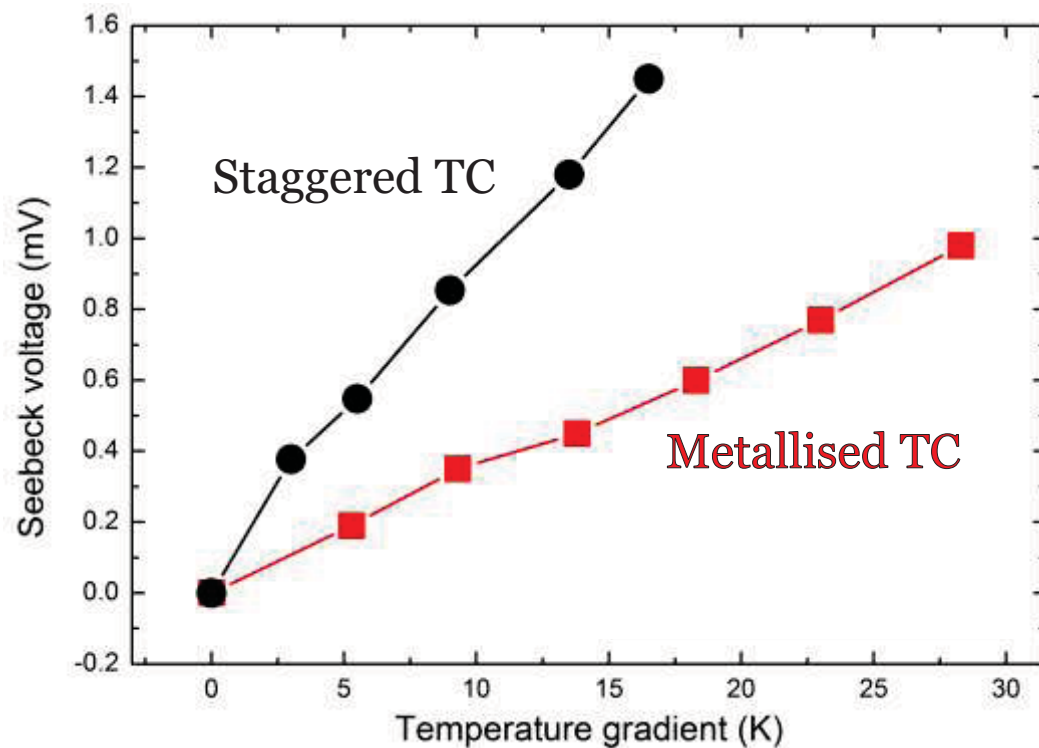


- Resulting max. Seebeck coefficient for a TC **~170 μ V/K (staggered design)**

- 14
- Max. output voltage **~10mV** (not shown)

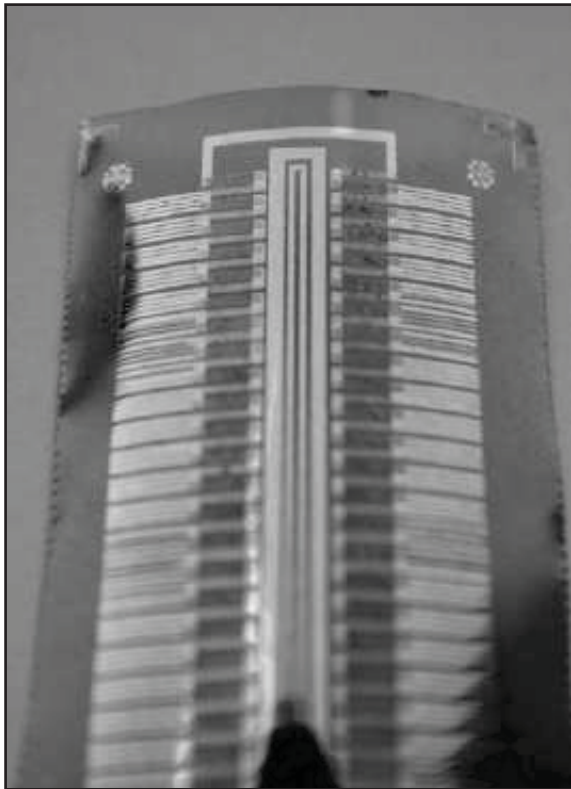
4. Metallisation

- Improves junction contact, but increases reverse diode current + reduces Seebeck voltage!
- In some cases: cracking of TE elements!



5. Comparison with conventional TEGs (I)

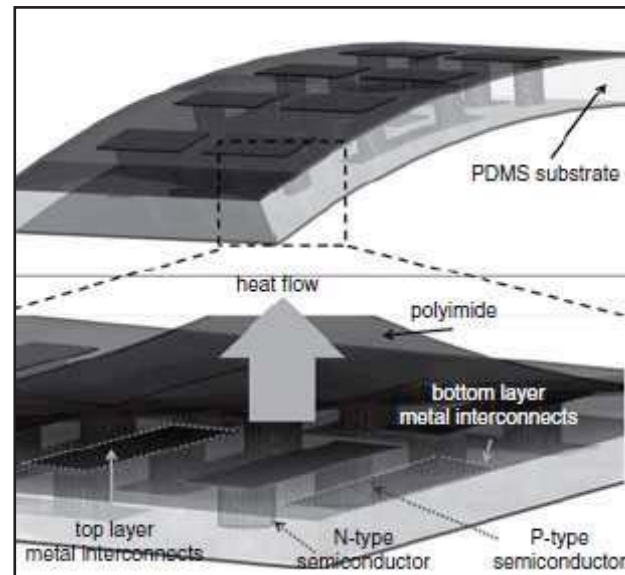
Francioso et al., J Power Sources
(2011)



Delaizir et al.,
Sensor Actuat A-Phys (2012)



Jo et al., Electron Lett (2012)



5. Comparison with conventional TEGs (II)

Device	(Francioso et al. 2011)	(Delaizir et al. 2012)	(Jo et al. 2012)	This study					
Design	Lateral/lateral	Vertical	Vertical	Lateral/lateral					
Substrate	polyimide (PI)	PI	PDMS	PDMS/glass					
Inactive to active Material ratio	0.23	0.88/3	1.75/27.4	1.47					
Resistance/ leg pair [Ω]	3.8×10^3	394	21.25	$\sim 10^4$					
Seebeck cf./ leg pair [$\mu\text{V}/\text{K}$]									
Material	Device	409	108	350	210	-	93	235	~ 170
Max. el. Power/ leg pair [μW] ($\Delta T=30\text{K}$)		0.00019		0.05		0.56		0.0013	
Efficiency factor [$\mu\text{W}/\text{K}^2\text{cm}^2$]		1.6×10^{-5}		$1.8 \times 10^{-3}/1.3 \times 10^{-3}$		$2.8 \times 10^{-3}/1.0 \times 10^{-4}$		1.299×10^{-4}	
Leg pairs/ area [cm^{-2}]		~ 76		$\sim 33/25$		4.5/0.16		~ 90	

From: Glatz et al., J Microelectromech S (2009)

6. Conclusions

- LIFT presented as **additive direct-write** tool for **microfabrication**
- Demonstrated **working thermoelectric generator** (TEG) on **polymer-coated** substrate
- Key results:
 - Sequentially LIFTed device elements
 - Seebeck coefficient/TC: **$\sim 170 \mu\text{V/K}$**
 - Performance comparable with other lateral-lateral TEGs on polymer
- **Future:** transfer of more complex TE materials, use of fully flexible substrate, Metal electrodes via LIFT

Acknowledgements

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LIFT at the University of Southampton: <http://www.orc.soton.ac.uk/lift.html>